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OF MANUFACTURE***C04B 37/02* (2006.01)*H01L 23/373* (2006.01)(71) Applicant: **SEMICONDUCTOR COMPONENTS  
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11, 2018, now Pat. No. 11,419,217, which is a divi-  
sion of application No. 15/206,574, filed on Jul. 11,  
2016, now Pat. No. 9,883,595, which is a division of  
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now Pat. No. 9,408,301.**Publication Classification**(51) **Int. Cl.***H05K 3/06* (2006.01)  
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**ABSTRACT**

A power electronic substrate includes a metallic baseplate having a first and second surface opposing each other. An electrically insulative layer also has first and second surfaces opposing each other, its first surface coupled to the second surface of the metallic baseplate. A plurality of metallic traces each include first and second surfaces opposing each other, their first surfaces coupled to the second surface of the electrically insulative layer. At least one of the metallic traces has a thickness measured along a direction perpendicular to the second surface of the metallic baseplate that is greater than a thickness of another one of the metallic traces also measured along a direction perpendicular to the second surface of the metallic baseplate. In implementations the electrically insulative layer is an epoxy or a ceramic material. In implementations the metallic traces are copper and are plated with a nickel layer at their second surfaces.

